PROCEEDINGS OF SPIE

Advanced Etch Technology and Process Integration for Nanopatterning X

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Editors

22–26 February 2021
Online Only, United States

Sponsored and Published by
SPIE

Volume 11615

Proceedings of SPIE 0277-786X, V. 11615

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Please use the following format to cite material from these proceedings:
Author(s), "Title of Paper," in *Advanced Etch Technology and Process Integration for Nanopatterning X*, edited by Julie Bannister, Nihar Mohanty, Proceedings of SPIE Vol. 11615 (SPIE, Bellingham, WA, 2021) Seven-digit Article CID Number.

ISSN: 0277-786X
ISSN: 1996-756X (electronic)

ISBN: 9781510640634
ISBN: 9781510640641 (electronic)

Published by
SPIE
P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time)· Fax +1 360 647 1445
SPIE.org

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